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PATENT

ATTORNEY DOCKET NO. 046124-5390

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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In re Application of: Kenshi FUKUMITSU et al.)
U.S. Application No.: 10/537,510) Confirmation No.: 4526
Filed: June 3, 2005) Examiner: Unassigned
For: LASER PROCESSING APPARATUS)
AND LASER PROCESSING METHOD)

Commissioner of Patents
MAIL STOP AMENDMENT

Sir:

INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicants bring to the attention of the Examiner the documents listed on the attached PTO-1449. This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits for the above-referenced application.

An International Search Report (ISR) dated March 23, 2004 is attached together with a copy of each document listed on the PTO Form 1449 that is not a U.S. patent or U.S. patent publication.

Applicants respectfully request that the Examiner consider the listed documents and evidence that consideration by making appropriate notations on the attached form. As for any document listed on the accompanying PTO-1449 that is in a language other than English, relevance can be understood from an enclosed English abstract or at least partial translation or from mention in the specification or in a search report for a corresponding application.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that the listed documents are material or constitute "prior

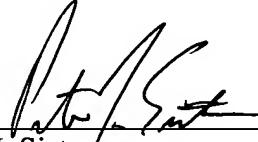
art." If it should be determined that any of the listed documents do not constitute "prior art" under United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such document.

Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over any of the listed documents, should any of the documents be applied against the claims of the present application.

Except for issue fees payable under 37 C.F.R. § 1.18, the Commissioner is hereby authorized by this paper to charge any additional fees during the entire pendency of this Application, including fees due under 37 C.F.R. § 1.16 and 1.17 which may be required and including any required extension of time fees, *or* credit any overpayment to Deposit Account No. 50-0573. This paragraph is intended to be a **CONSTRUCTIVE PETITION FOR EXTENSION OF TIME** in accordance with 37 C.F.R. § 1.136(a)(3).

Respectfully submitted,

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Dated: December 8, 2005

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INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	Attorney Docket No.: 046124-5390	Serial No.: 10/537,510
	Applicants Kenshi FUKUMITSU et al.	Page 1 of 1
PTO Form 1449	Filing Date: June 3, 2005	Confirmation No.: 4526

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub Class	<u>Translation</u>	YES	NO
		2002-219591 A	Aug. 6, 2002	JP			Abstract		
		1 338 371 A1	Aug. 27, 2003	EP					
		2001-340979 A	Dec. 11, 2001	JP			Abstract		
		2000-084688 A	Mar. 28, 2000	JP			Abstract		
		11-104873 A	Apr. 20, 1999	JP			Abstract		
		09-019784 A	Jan. 21, 1997	JP			Abstract		

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Kiyotaka MIURA et al., "Formation of Photo-induced Structures in Glasses with Femtosecond Laser," Dai 42 Kai Proceedings of Laser Materials Processing Conference, 1997, pp. 105-111.

Ken-ichi HAYASHI, "Inner Glass Marking by Harmonics of Solid State Laser," Dai 45 Kai Proceedings of Laser Materials Processing Conference, 1998, pp. 23-28.

Tomokazu SANO et al., "Ultrashort Pulse Laser Microprocessing of Silicon," Short Pulse and Short Wavelength Laser Precision Microprocessing of Electric Materials (first report), 2000, pp. 72-73.

Shuji TAKAOKA, "Principle and Characteristics of Stealth Dicing Technology Optimal for Dicing of Ultrathin Semiconductor Wafer," Denshi Zairyō, September 1, 2002, pp. 17-21.

Examiner _____ **Date Considered** _____

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.